

Institute for Nanometre Optics and Technology

Nanometre Optics Technologies at Helmholtz Centre Berlin

Alexei Erko



1st example: vitrified product concentrate:

Every day millions of tons of vitrified industrial waste are on the way to storage facilities around the world.





Pacific Heron, one of PNTL's transport ships (Image: PNTL)

What is vitrification?

The embedding of material in a glassy matrix.





Artificial aging of waste glasses

Annealing at 600° and 800° C





The embedding of material in a glassy matrix.

F. Pinakidou, M. Katsikini, E. C. Paloura, P. Kavouras, Ph. Komninou, Th. Karakostas, A. Erko, NIM, B246 (2006) 238



Toxic crystals: Fe, PbFe₁₂O₁₉

Cultural Heritage. Non-destructive Testing

I. Reiche, J. Riederer (Staatl. Museen Berlin), M. Radtke, S. Merchel, A. Berger (BAM)



Composition of Dürers



Albrecht Dürer "Thronender Bischof; Brustbild eines Mannes mit Pelzmütze" (1521)

A result: "Bischof" and "Mann mit Pelzmütze" have been drawn using different pencils.

Cultural Heritage. Non-destructive Testing

E. Pernicka (TU Freiberg), C.-H. Wunderlich (LfA Halle), M. Radtke, H. Riesemeyer (BAM) Gold composition analysis of the Nebra Skydisk (3600 v. Chr)





Nanometre optics are a crucial tool for research at new and existing light sources



Expanding the figure accuracy of SR-Optics to the size of Germany – the Zugspitze would be a peak of 5 mm only !

What are the requirements?





Metrology at the INT HZB



- NOM / LTP-II
- Micromap (2.5x, 5x, 10x, 20x, 50x)
- AFM
- Interferometer ZYGO-GPI

In-Situ

- Optics Beamline
- Reflectometer
- Polarimeter
- Focus measuring camera

Theory

Zentrum Berlin

- software library for beamline optics design
- WAVE / PHASE / ...







Micro&Nano technology. Highlights 2010-2011

Nano zone plate technology



X-ray microscope (TXM) image of a Cr/B_4C multilayer structure with 5 different periods recorded in the third order of diffraction with a 20 nm d_{rn} zone plate. Photon energy 700eV, $\Delta E/E = 13800$, exposure time 30 s, pixel-size 2.0 nm.

S. Werner, S. Rehbein, P. Guttmann, S. Heim, G. Schneider, Microelectron. Eng. 87 (2010), 1557-1560

Thermoforming, Soft Lithography



Replicated polymer part fabricated by replica molding. Optical lens surface.

T. Senn, Ch. Waberski, J. Wolf, J.P. Esquivel, N. Sabaté, **B. Löchel**, Microelectron. Eng. 88 (2011), 11–16

Optical nano-metrology





Kirckpatrik-Baez-HFM – horizontal focussing mirror for X-FEL: inspection at the HZB-NOM

F. Siewert et al.: The first diffraction limited KB-focusing mirror pair for the LCLS *to be published*

The main principle: Holographic process







The scheme of the hologram reconstruction experiment at BESSY beamline.



Information encoded in a hologram.



Image in SEM of a hologram structure fabricated in AZM.

Reconstruction of the hologram at BESSY beamline.

Elliptical reflection zone plate



Off-axis part of RZP

Modified reflection zone plate



Elliptical modified reflection zone plate combining the first, third and fifth diffraction orders in the sagittal direction. In the meridional (beam) direction only the first order is used. Technological resolution limit 20 nm

Calculated focal spot



Nanometer focusing of X-rays with modified reflection zone plates, A.G. Michette, A. Erko et al, Optics Communications, 245, (2005), 249–253.

X-ray beam focused in one direction to a width of 14 nm at 10 keV

1.0

0.8

0.6

0.4

0.2

0.0

-200

-150

-100

-50

Intensity (arb. unit)

Measurement

Calculation



Experimental set-up for a focusing measurement of the total reflection zone plate (TRZP).

Intensity distribution of measured (plotted data) and calculated (red line) linear focusing by the TRZP. The inset shows an enlargement of the main peak.

0

Position (nm)

0.5

0.0

50

0

100

150

20

200

Sub-15nm Hard X-Ray Focusing with a New Total-Reflection Zone Plate Hidekazu Takano et al, Applied Physics Express 3 (2010) 076702



2nd example: what is the time limit of magnetic switching?

A. Erko, A. Firsov, K. Holldack, AIP Conf. Proc. (2010) 1234, 177-180



Slicing facilities in the experimental hall

fs time-resolved dichroism

(energy window \approx 5 eV)





Slicing facilities in the storage ring

High Harmonics Generator Optics





Optics for Beam Manipulations: X-ray, IR, and Neutrons & Advanced Sample Management



Reflection Fresnel lens for THz spectromicroscopy

Antenna for focusing IR radiation



Parallel X-ray Diffraction Fluorescence Spectrometer

Detector array



Spectrometer in vacuum vessel



DiS test at the UE52 SGM beamline BESSY II







Pixel

HIGHLY EFFICIENT BLAZED GRATINGS FOR X-RAYS

- Blazed gratings for X-Rays were fabricated only by Carl Zeiss
- Zeiss plans to stop fabrication of gratings soon
- A problem for HZB and all SR sources.

→ We want to establish a Technology Center for Highly Efficient Precision Gratings at HZB We received 5 M€ EFRE Funding

For this funding we want especially thank the Senate of Berlin

→ Aim of the center:

- Development of new technologies for blazed grating fabrication:
- Ruling technology, Interference lithography, Anisotropic crystal etching





Why blazed grating technology?







Rectangular profile

Production of mechanical ruling blazed gratings

Anisotropic etching technology







VISTEC EBPG5000plusES. Electron beam writing system.





Dr. Alexander Firsov Tel.: 030 8062-14667 | Fax: 030 8062-14682 alexander.firsov@helmholtz-berlin.de



Networks:











Cooperation:



Masken Lithographie & Consulting GmbH













PRESENT AND FUTURE OPTICAL ELEMENT PRODUCTION

